



אוניברסיטת בן-גוריון בנגב
Ben-Gurion University
of the Negev

Nano-Fabrication
Center

ALD ATSL



Description

The GEMStar XT Thermal table-top ALD is a thin film technology that enables applications of very precise nanometer-thick, smooth, pinhole-free and totally conformal thin films on any desired shape and geometry, results in high-aspect-ratio structures.

ALD applications: high quality dielectrics, diffusion barrier coatings, diffusion barrier coatings with low gas permeability

Specifications/Capabilities

Wafer size: up to 8" (200mm)

Deposition materials available: Aluminum oxide, Zinc oxide

Process range temperatures: up to 300°C

Link

[ATSL - Advanced Technological Solutions Ltd. - Atomic Layer Deposition \(ALD\)](#)